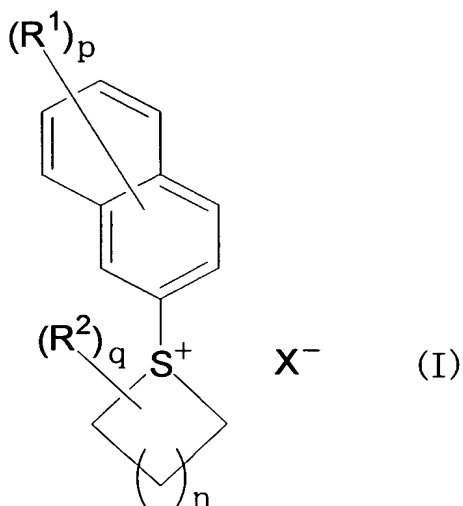


## ABSTRACT OF THE DISCLOSURE

A sulfonium salt compound excelling in transparency to deep ultraviolet rays at a wavelength of 220 nm or less, exhibiting well-balanced excellent performance such as sensitivity, resolution, pattern form, LER, and storage stability when used as a photoacid generator, a photoacid generator comprising the sulfonium salt compound, and a positive-tone radiation-sensitive resin composition containing the photoacid generator.

The sulfonium salt compound is shown by the following formula (I),



wherein  $R^1$  represents a halogen atom, an alkyl group, a monovalent alicyclic hydrocarbon group, an alkoxyl group, or  $-OR^3$  group, wherein  $R^3$  is a monovalent alicyclic hydrocarbon group,  $R^2$  represents a (substituted)-alkyl group or two or more  $R^2$  groups form a cyclic structure,  $p$  is 0-7,  $q$  is 0-6,  $n$  is 0-3, and  $X^-$  indicates a sulfonic acid anion.

The positive-tone radiation-sensitive resin composition comprises (A) a photoacid generator of the sulfonium-salt compound and (B) an acid-dissociable group-containing resin.